

In the claims.

Please amend the claims as follows:

1. (currently amended) A maskless lithography system comprising an array of focusing elements, each of which focuses [~~an energy~~] a photon beam from an array of photon sources into an array of focal spots on an adjacent substrate in order to create a permanent pattern on [~~an~~] the adjacent substrate.
2. (original) The maskless lithography system as claimed in claim 1, wherein said array of sources includes an array of light emitting diodes.
3. (original) The maskless lithography system as claimed in claim 1, wherein said array of sources includes an array of semiconductor lasers.
4. (original) The maskless lithography system as claimed in claim 1, wherein said array of sources includes an array of vertical cavity surface emitting lasers.
5. (original) The maskless lithography system as claimed in claim 1, wherein said array of focusing elements includes an array of diffractive elements.
6. (original) The maskless lithography system as claimed in claim 1, wherein said array of focusing elements includes an array of Fresnel lenses.
7. (original) The maskless lithography system as claimed in claim 1, wherein said system further includes an array of microlenses interposed between said array of sources and said array of focusing elements.
8. (currently amended) A maskless lithography system comprising an array of focusing

elements, an array of microlenses, and an array of [~~energy~~] photon sources, wherein each photon energy source is positioned to selectively direct energy through a microlens toward a focusing element, and each focusing element is positioned to direct a focused beam [~~toward~~] onto a substrate to create a permanent pattern thereon.

9. (original) The maskless lithography system as claimed in claim 8, wherein said array of sources includes an array of light emitting diodes.

10. (original) The maskless lithography system as claimed in claim 8, wherein said array of sources includes an array of semiconductor lasers.

11. (original) The maskless lithography system as claimed in claim 8, wherein said array of sources includes an array of vertical cavity surface emitting lasers.

12. (original) The maskless lithography system as claimed in claim 8, wherein said array of focusing elements includes an array of diffractive elements.

13. (currently amended) A maskless lithography system comprising an array of Fresnel lenses, each of which focuses [~~an energy~~] photon beam from an array of photon sources into an array of focal spots on an adjacent substrate in order to create a permanent pattern on [~~an~~] the adjacent substrate.

14. (canceled)

15. (canceled).

16. (currently amended) A maskless lithography system comprising an array of photon sieves, each of which focuses [~~an energy~~] a photon beam from an array of photon sources into an array of

focal spots on an adjacent substrate in order to create a permanent pattern on [~~an~~] the adjacent substrate.